

Supplementary Materials: Bifunctional TiO₂/AlZr Thin Films on Steel Substrate Combining Corrosion Resistance and Photocatalytic Properties

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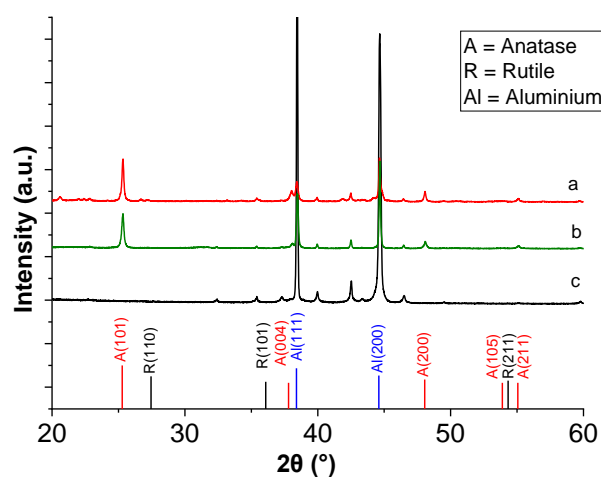


Figure S1. XRD Patterns for TiO₂/Al-Zr thin films without microflowers deposited at (a) 500 °C, (b) 550 °C and (c) Al-Zr.

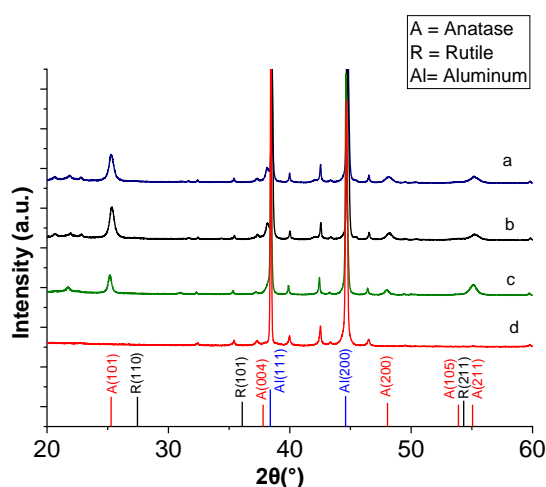


Figure S2. XRD patterns for TiO₂/Al-Zr thin films with microflowers deposited at (a) 550 °C, (b) 540 °C and (c) 500 °C on (d) Al-Zr.

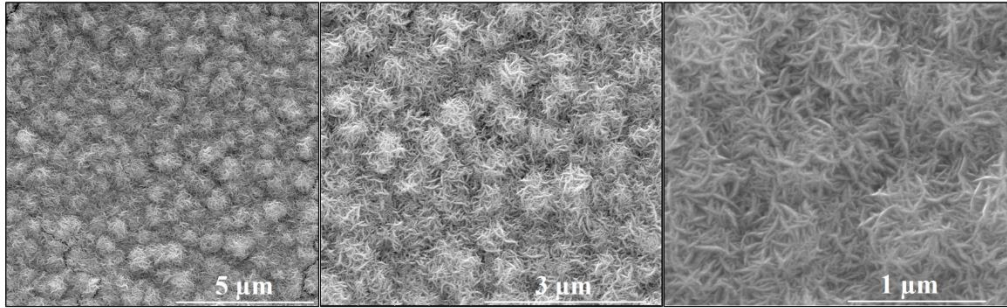


Figure S3. SEM images of TiO₂/Al-Zr film without microflowers deposited at 550 °C.

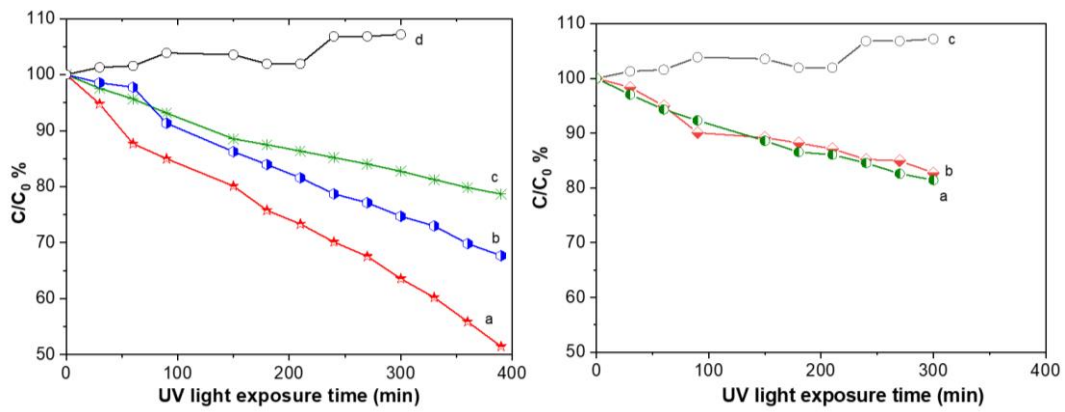


Figure S4. Decomposition of Orange G by TiO₂/Al-Zr thin films with microflowers (**left**) deposited at (a) 550°, (b) 540 °C, (c) 500 °C and (d) Al-Zr as underlayer under UV light (371 nm) irradiation time. TiO₂/Al-Zr thin films without microflowers (**right**) deposited at (a) 500 °C and (b) 550 °C and (c) Al-Zr as underlayer under UV light (371 nm) irradiation time.



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